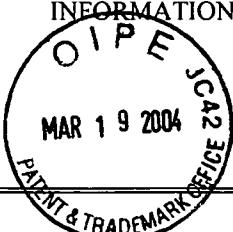


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INFORMATION DISCLOSURE STATEMENT BY APPLICANT
(Use several sheets if necessary)

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*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
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2.	5,216,257	Jun. 1, 1993	Brueck et al.	250	548	7/9/1990
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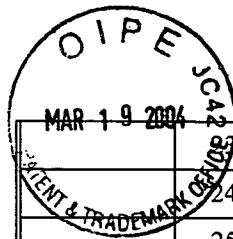
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	Document	Date	Country	Class	Subclass	Yes	No
20.	WO 01/84382 A1	Nov. 8, 2001	PCT	G06F	17/50	5/4/2000	
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Examiner

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